

Image sensing technologies, challenges and vision

반도체
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Image Sensor



- Semiconductor device converting light to digital signal



<https://news.samsung.com/>

Photons



Optics/device
design

Electrons



Device/analog
design

Voltage Signal



Mixed signal design

Digital number

.....
**In millions
parallel manner**

Image Sensor and Pixel

Pixel: Picture element → Technology aware design

- State of the art CIS for consumer application
: Back-side illumination, Stacked (TSV, hybrid-bonding)



Apple iPhone 13 Pro

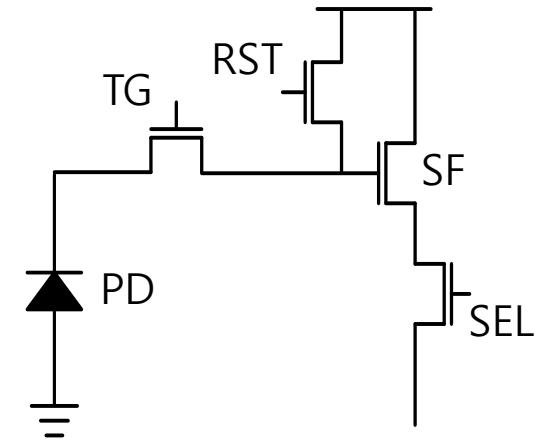
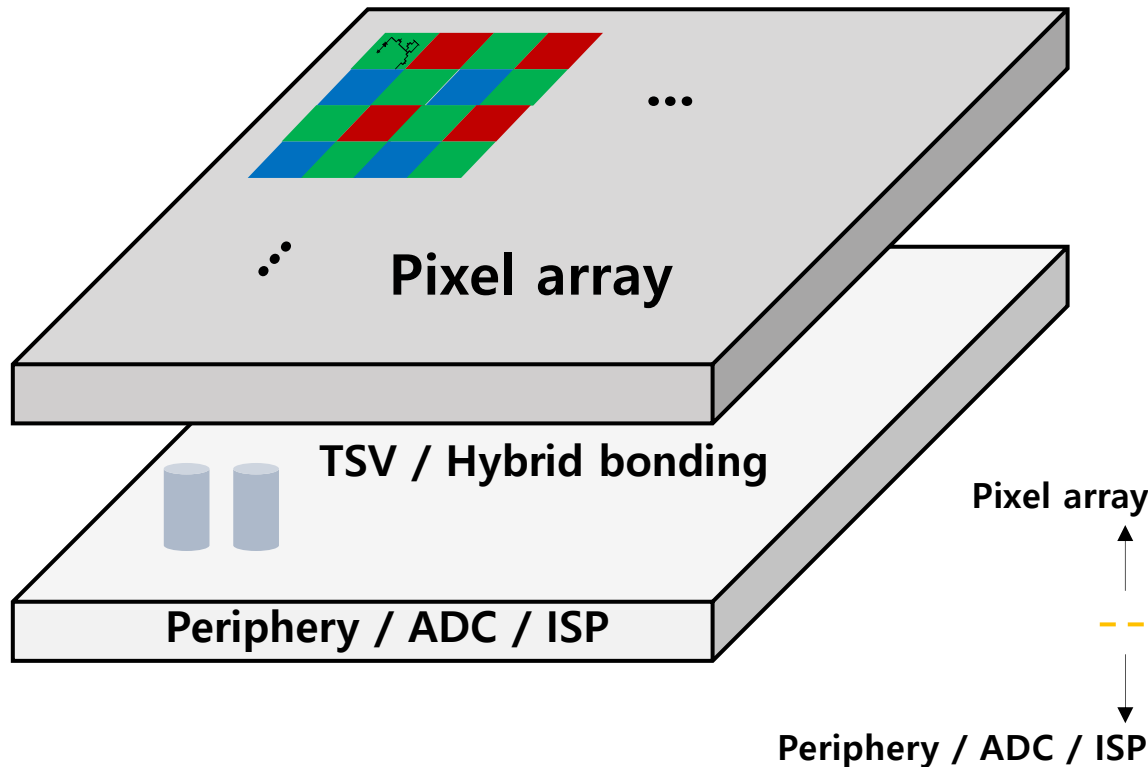
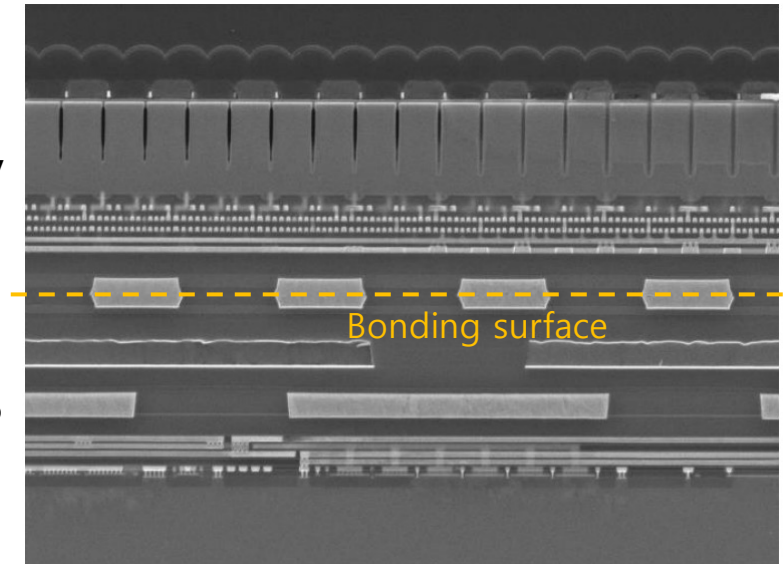


Image sensor pixel

1PD and 3-transistors

Transistors can be shared (2, 4, 8-shared)



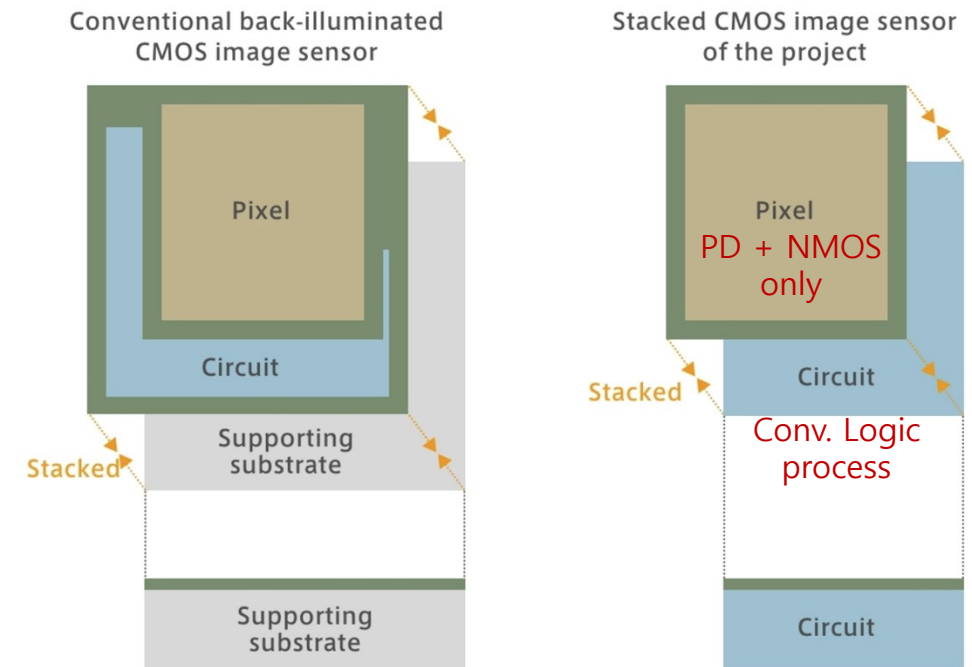
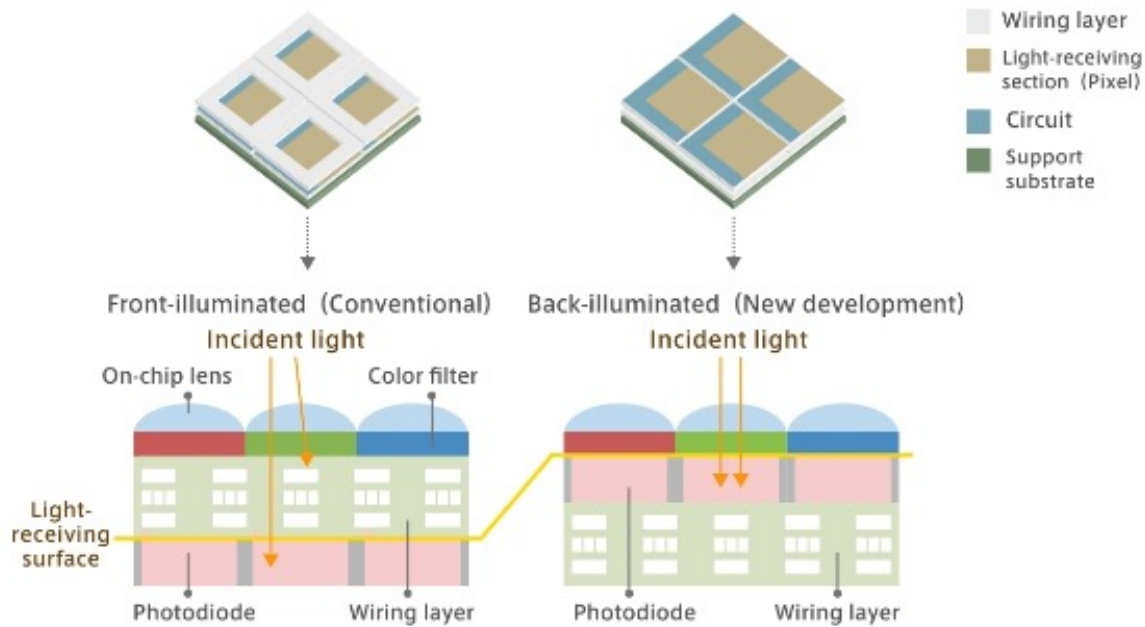
Sony IMX260, picture from IISW 2017 Tech Insights

3D integration in CMOS Image sensor

- 10-years since first commercialization
- Back side illumination for efficient photon collection
 - Chip stacking for separate optimization
 - Pixel (Photodiode) vs. Readout circuit (tr)

Front side illumination

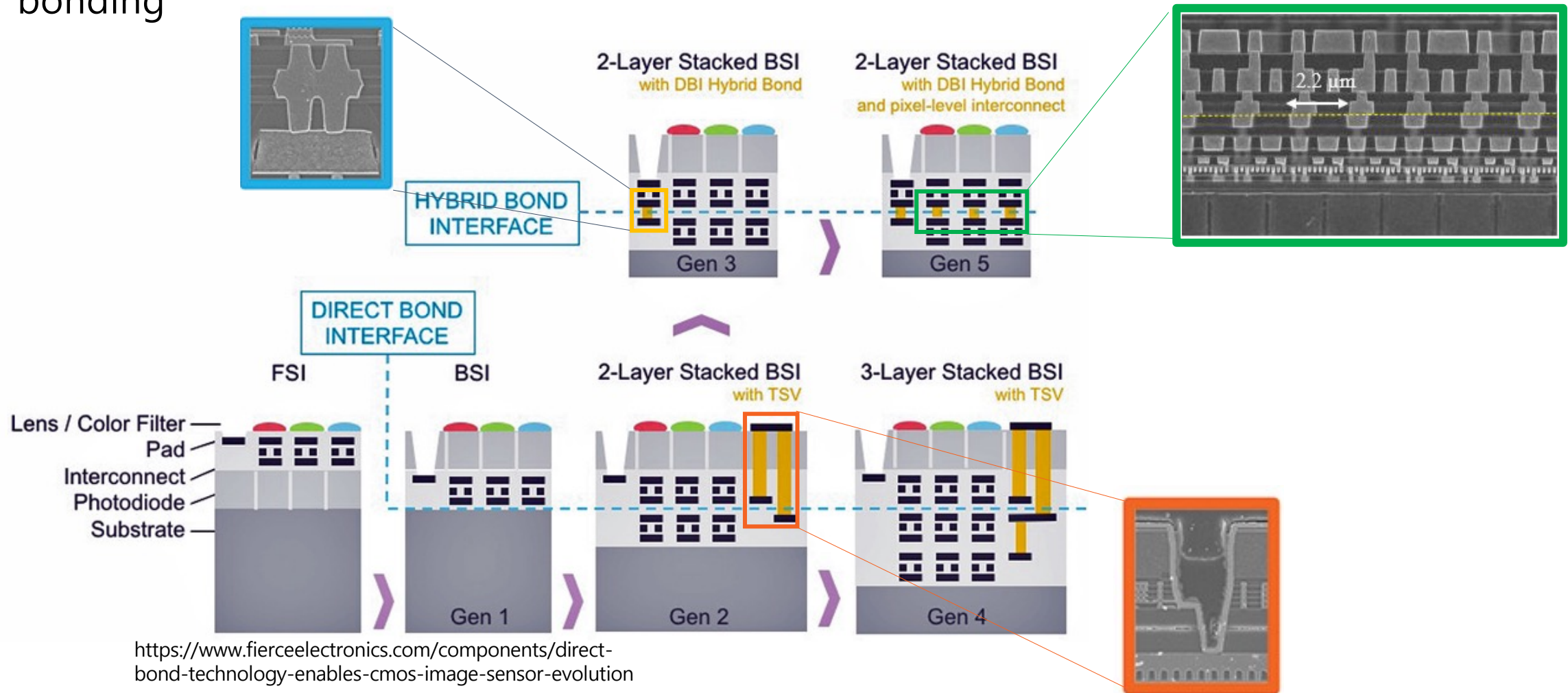
Back side illumination



*From Sony

Stacking technology

Chip stacking after processed then connected by **TSV** (Through Silicon Via) vs. **Cu-Cu Hybrid bonding**

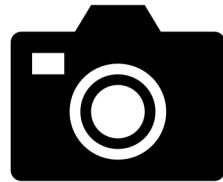


Paradigm shift in image sensing

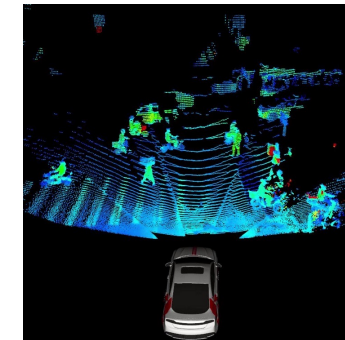
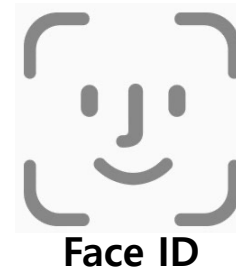
- Heart of the camera

Photography

- Compact / DSLR / smartphone cameras

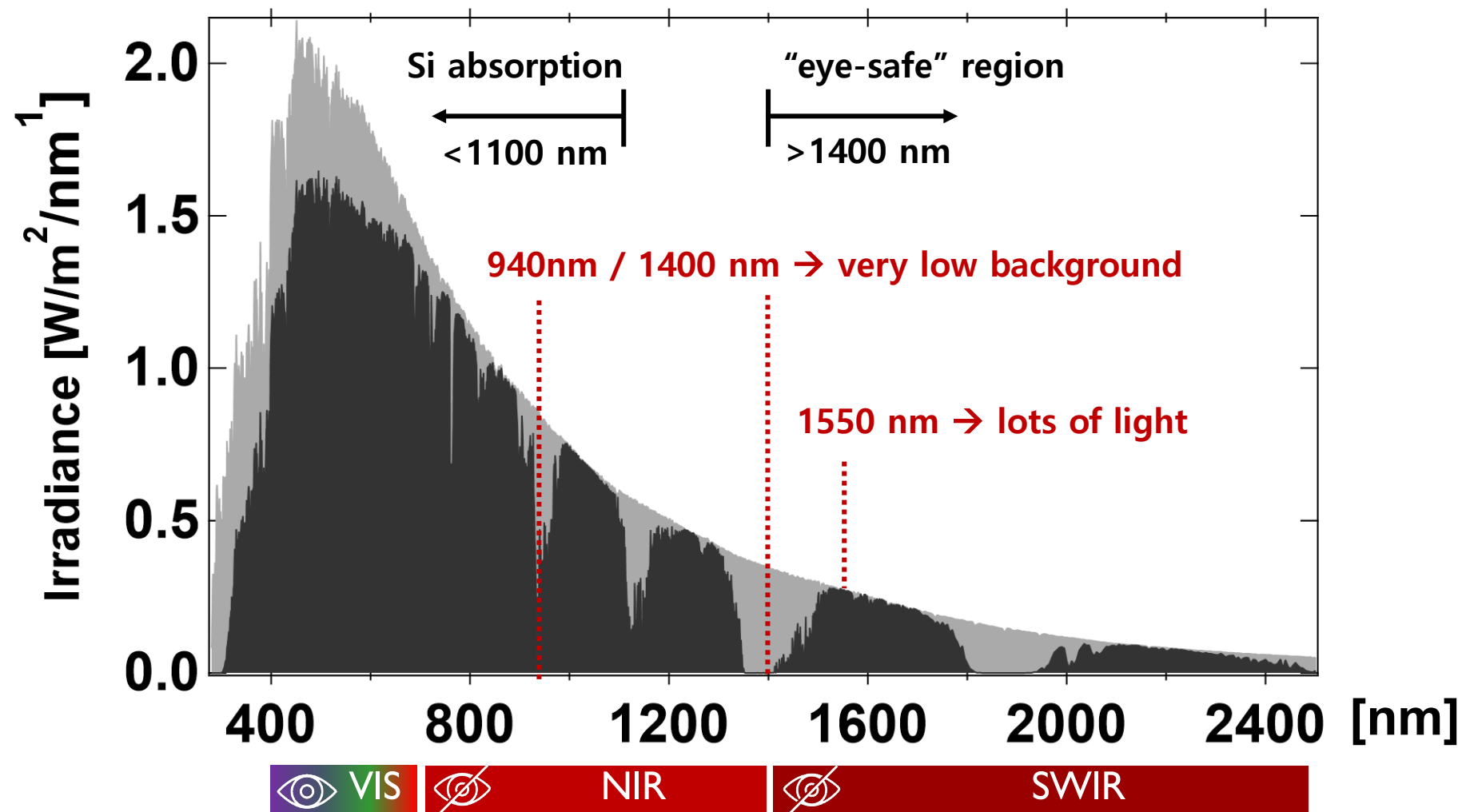


from picture taking...



...to information acquisition

Infrared: NIR / SWIR

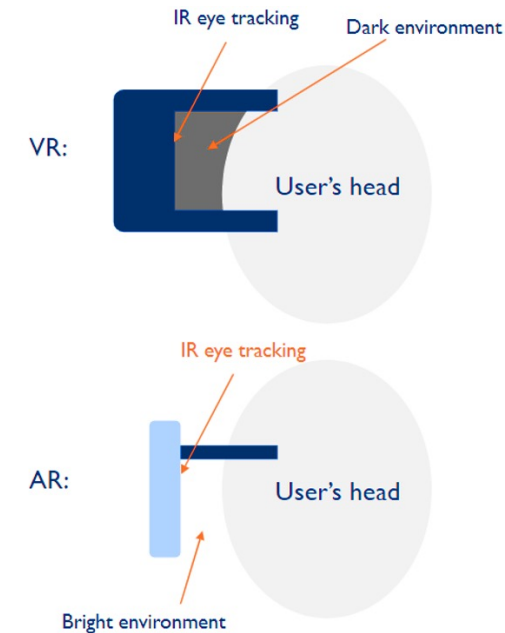
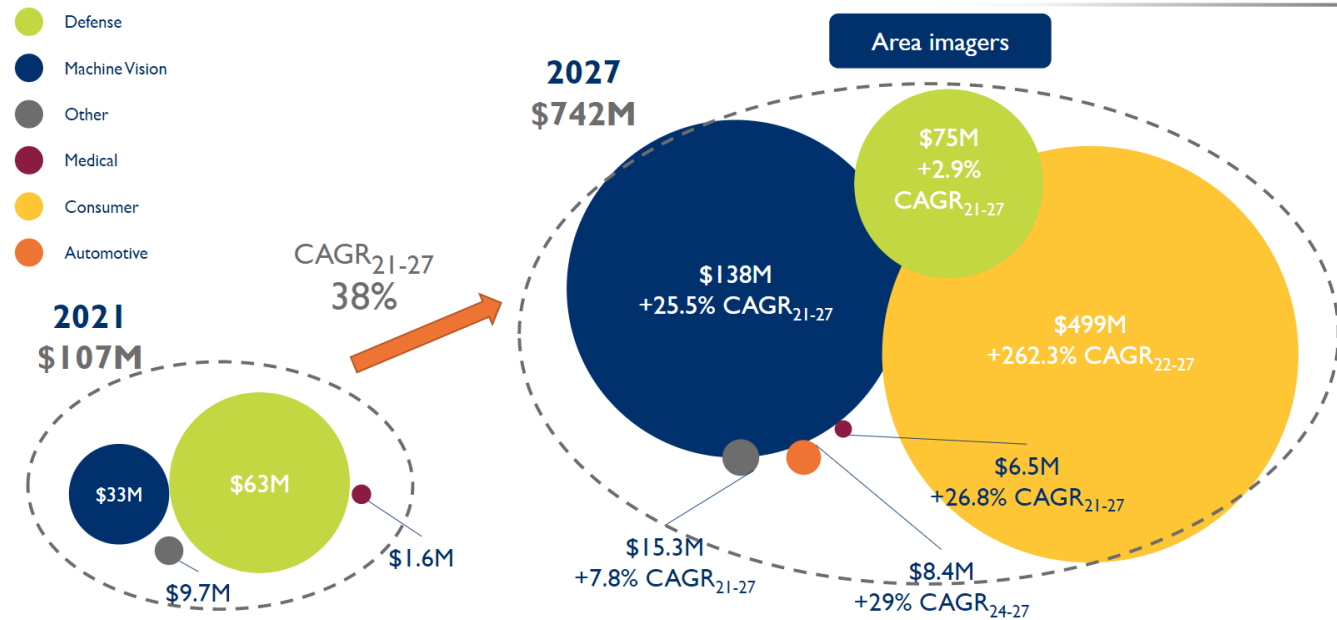


SWIR Market Opportunity

- Emerging SWIR Market
 - Machine Vision / Consumer

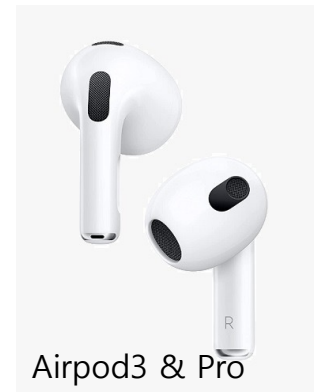
*Source: Yole SWIR Imaging 2022

AREA IMAGERS – MARKET OVERVIEW



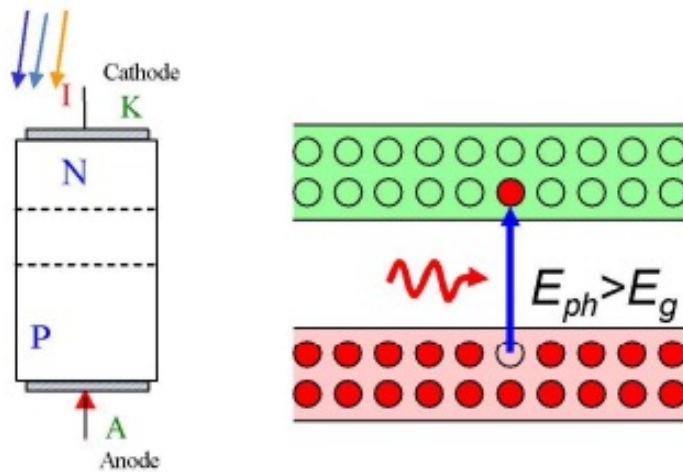
From Yole, 'SWIR report' 2022

Iphone 14 Pro

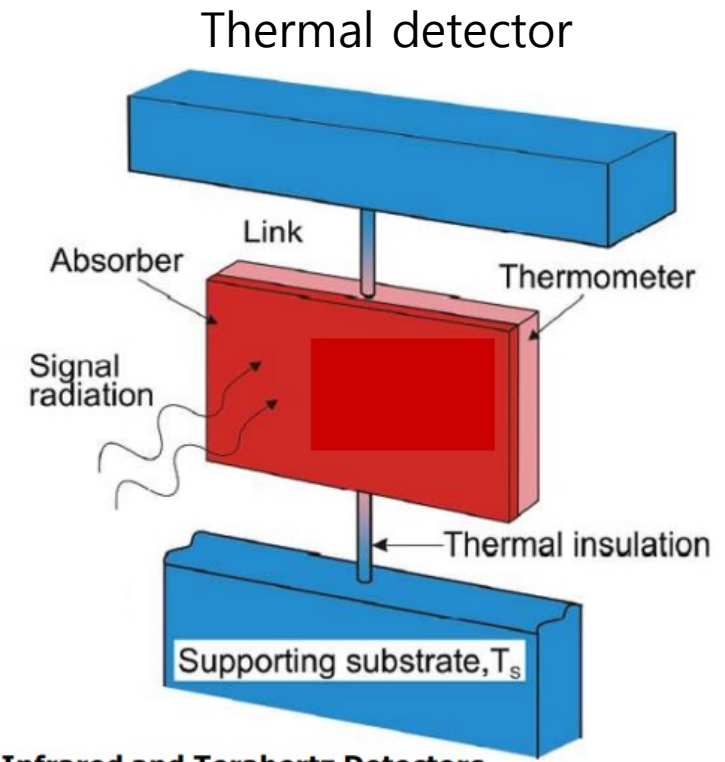


How to address imaging from UV to LWIR

- Use either Photodetector (mostly photodiode) or Thermal detector
 - Use a semiconductor material to convert incident photons to electrical charges
$$\frac{hc}{\lambda} > E_g \Rightarrow \frac{1.24}{E_g} = \lambda_c \text{ Cut-off wavelength}$$
 - Silicon ($E_g = 1.12\text{eV}$), $\lambda_c \mu\text{m}$, Near Infrared (NIR)



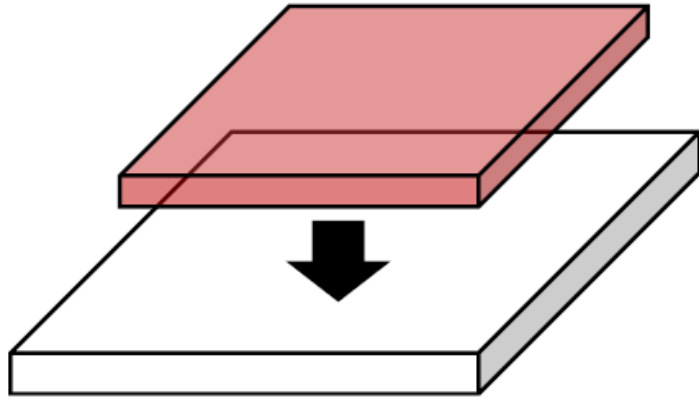
Photodetector



Infrared and Terahertz Detectors,
A. Rogalski, CRC Press (2019)

How to extend wavelength

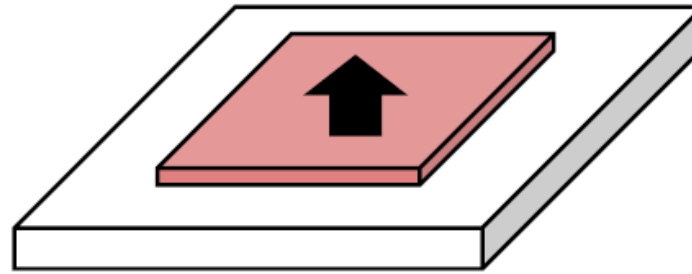
Choose the (non-Si) **absorber** and get it on the readout



bond



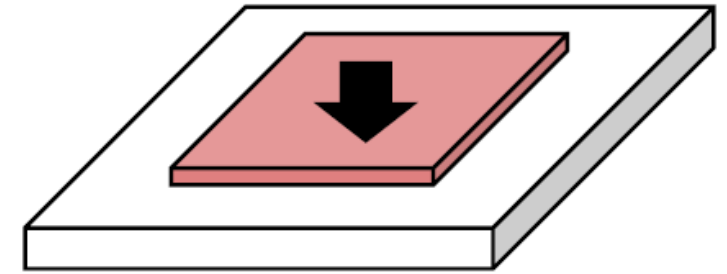
InGaAs
HgCdTe
...



grow



Ge / SiGe
InGaAs
...



deposit



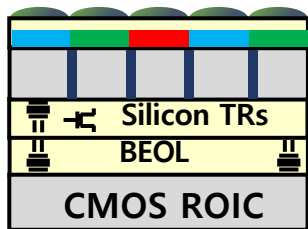
quantum dot (QD)
organic (OPD)
perovskite (PePD)
...

QD (Quantum Dot) image sensor

Si CIS

visible

- ✓ high maturity
- ✓ high throughput / monolithic
>6B units/year!
- ✓ low cost
single \$ per camera
- ✗ no SWIR EQE
Si transparent above 1 μm
- ✓ small pixel pitch / high resolution
SotA CIS 0.56 μm

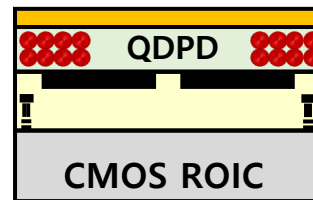


SotA CIS x5 pixels

QD TFPD

visible – NIR – SWIR - eSWIR

- » maturing technology
- ✓ high throughput / monolithic
wafer-level process in preparation
- » low cost
target: 10\$ – 100\$
- ✓ good SWIR EQE
spectrum tunable per application
- ✓ small pixel pitch / high resolution
imec SotA $\leq 2 \mu\text{m}$

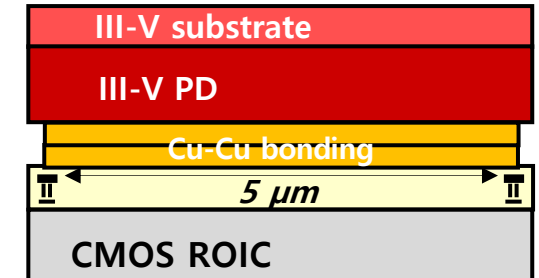


SotA QD x2 pixels

InGaAs, HgCdTe

short-wave infrared

- ✓ high maturity
- ✗ low throughput / hybrid
 $\sim 10\text{K}$ units/year
- ✗ high cost
several K\$ per camera
- ✓ high SWIR EQE
- ✗ large pixel pitch / low resolution
SotA InGaAs $\geq 5 \mu\text{m}$

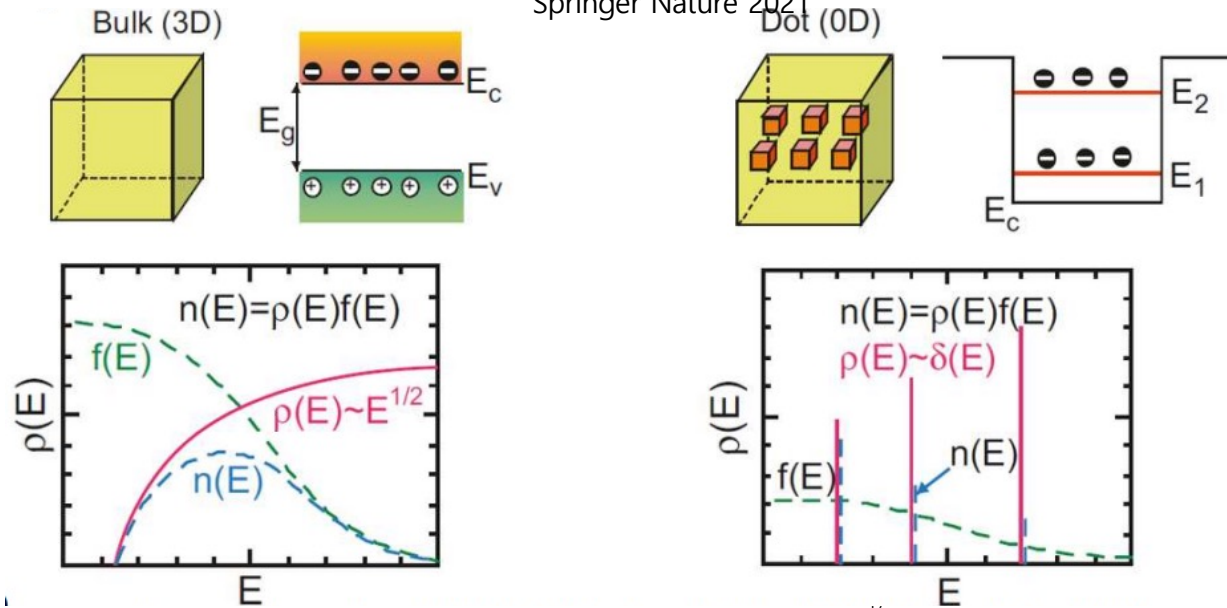


SotA InGaAs (Sony)

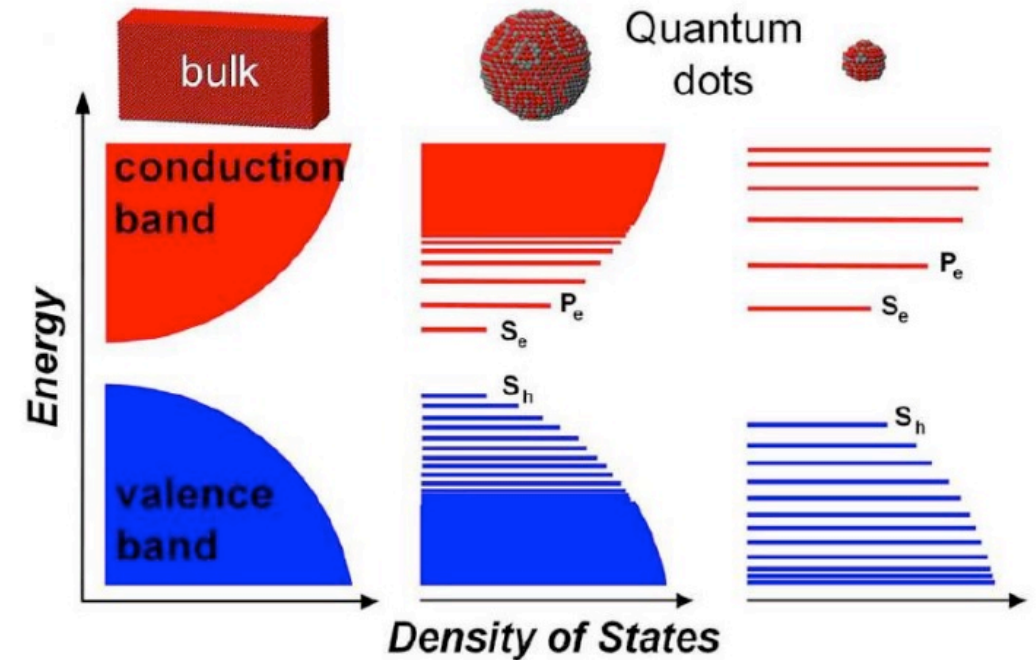
Quantum Confinement Effect

- QD feature discrete states whose energy depend on QD size (and shape)

Progress in quantum dots Photodetectors, A. Rogalski, Springer Nature 2021



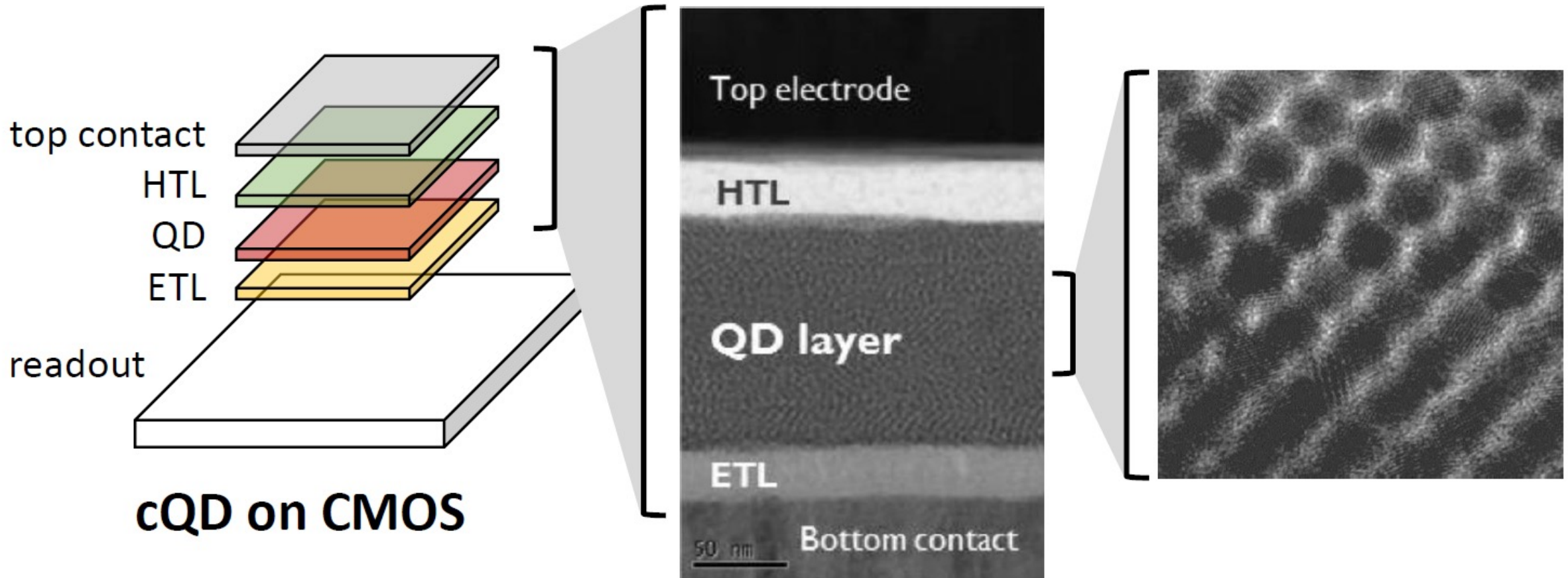
$\rho(E)$ density of states
 $f(E)$ Fermi dirac distribution



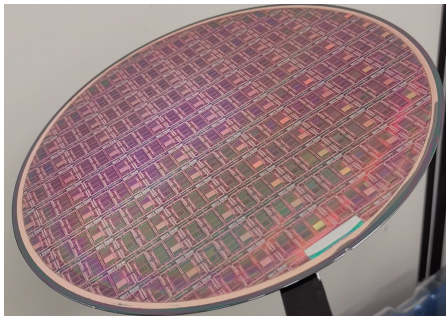
Building devices from colloidal quantum dots C. R. Kagan & al., Science, Issue 6302 2016

QD image sensor

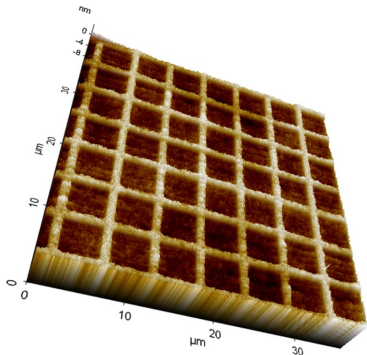
Monolithic integration of QDPD on Silicon ROIC



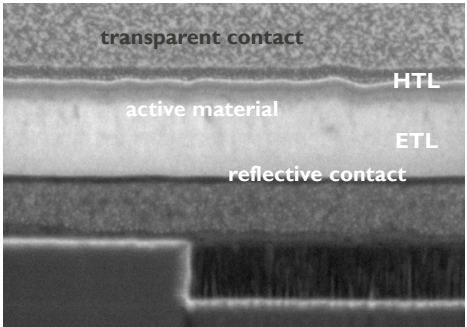
From QDPD to Image sensor – Monolithic integration on Si ROICs



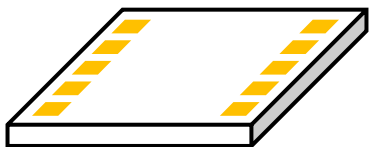
ROIC chips on 200 mm wafer



planarized contacts (<10 nm)



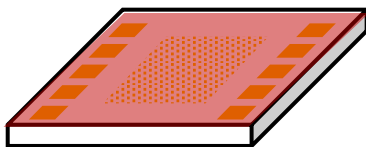
TFPD stack on flat ROIC



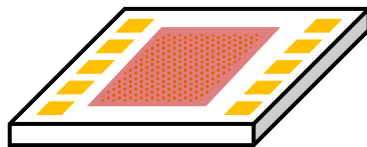
ROIC with contact pads



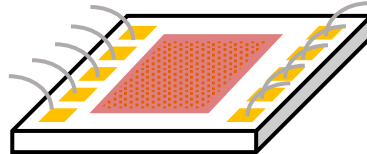
ROIC with planarized contacts



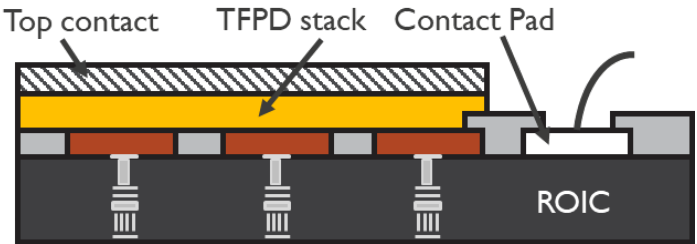
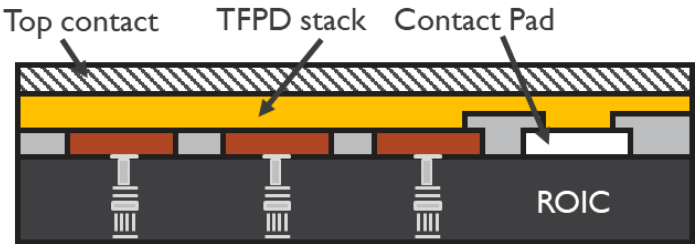
stack deposition (spin-coating or PVD)



stack patterning (pad access)

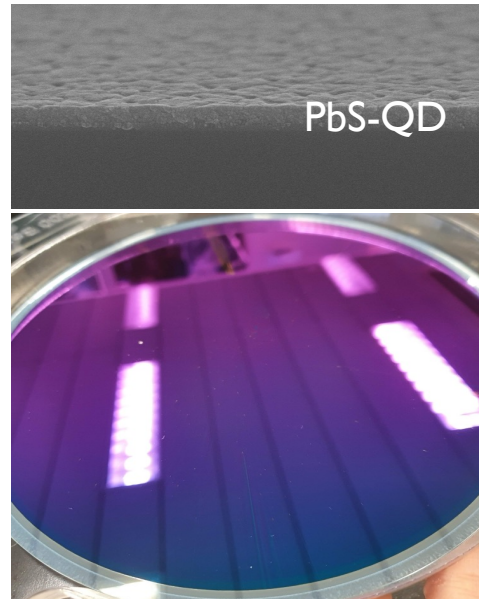
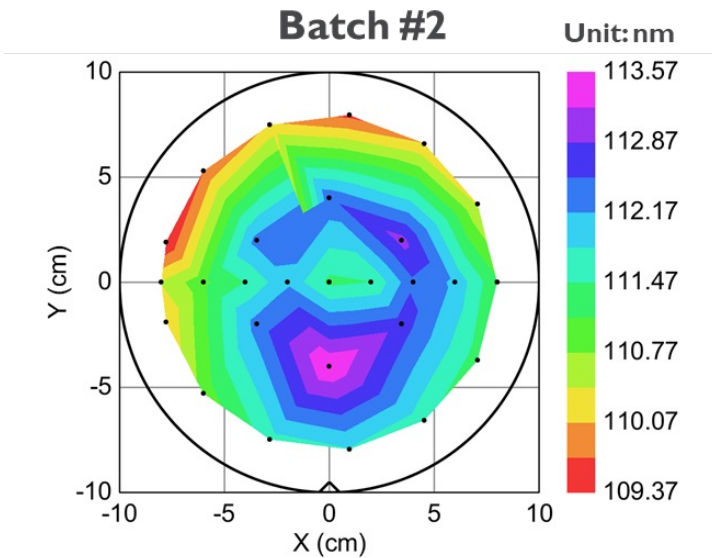


Packaging and testing

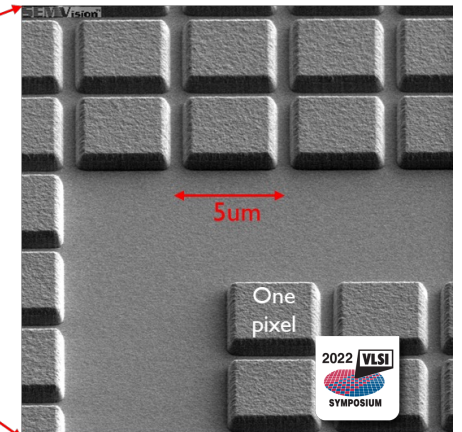
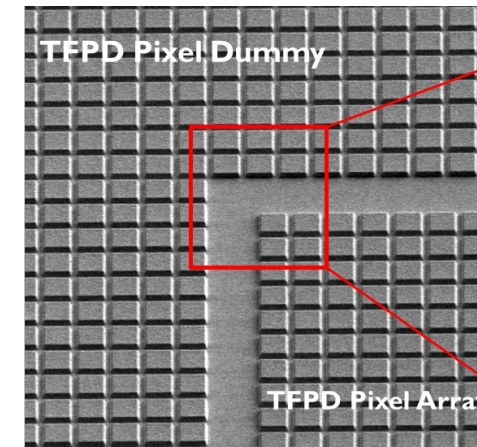
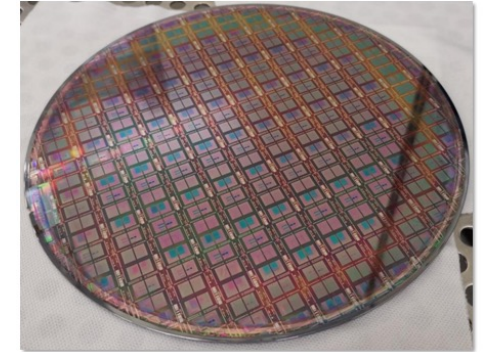
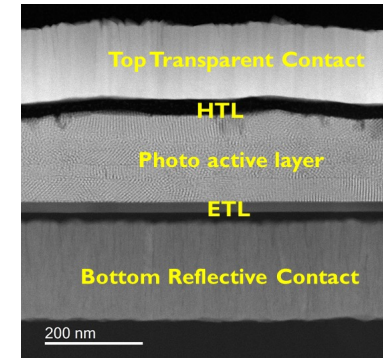


Pixelation - Wafer Level TFPD Stack Patterning

Wafer level TFPD stack deposition



Post TFPD Pixelation Litho (DUV)

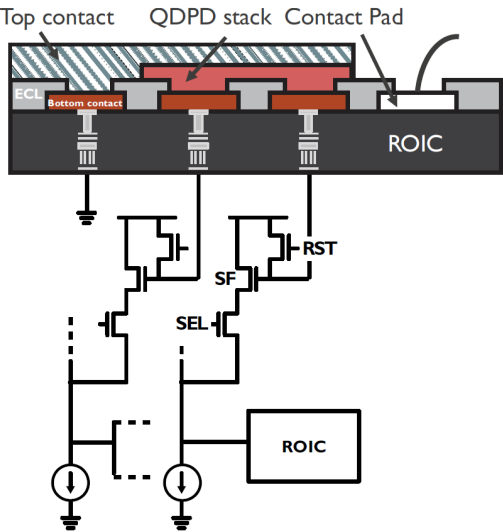
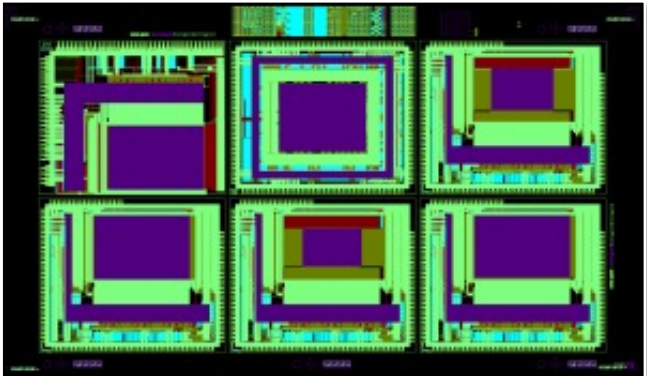


TFPD stack pixilation demonstrated at wafer level

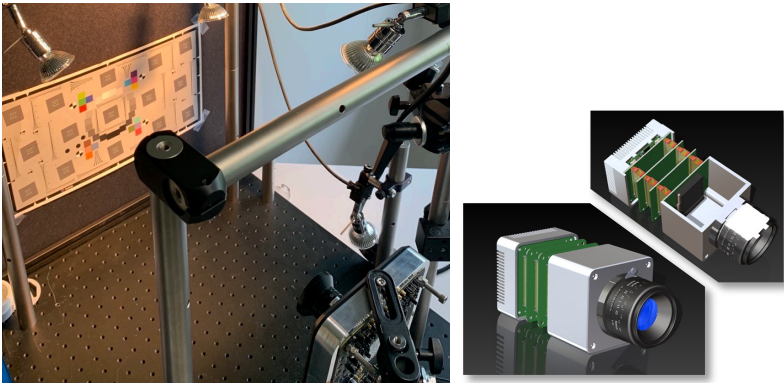
*Yunlong Li, Jiwon Lee et. al., VLSI 2022

QD SWIR Image sensor design and camera build

ROIC Design

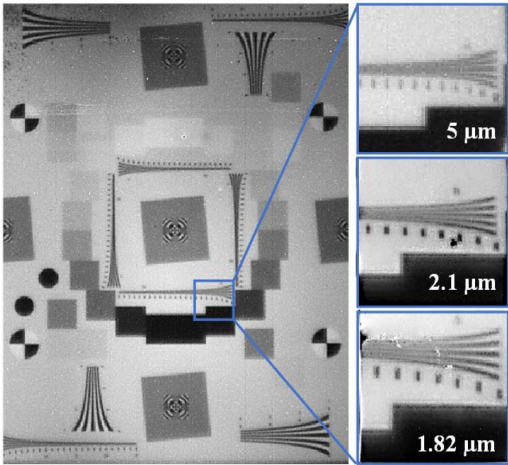


Camera build



Demonstration

IEDM 2020: J.Lee et al. 0.1109/IEDM13553.2020.9372018



Camera characterization

Parameter	gen1 [2020]		gen2 [2021]	Unit
Pixel pitch	5	1.82	5	μm
Resolution	768x512	128x128	768x512	px
DR	84	63	82	dB
FWC	470	16.8	325	Ke ⁻
J _D	0.3	0.2	3.3	μA/cm ²
RN	33	12	25	e ⁻
PRNU	1.3	1.8	2.4	%
λ _{PEAK}	1400		1450	nm
EQE	13		40	%

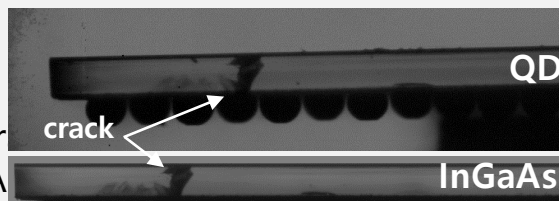
DR: dynamic range; FWC: full-well capacity; J_D: dark current density; RN: read noise; PRNU: photo-response non-uniformity; λ_{PEAK}: peak wavelength; EQE: external quantum efficiency

Imager Demonstration

What have we tested?

Benchmarking

Validation of the imec camera against an off-the-shelf InGaAs



QD imager (SWIR)

Security/surveillance (see through sunglasses)

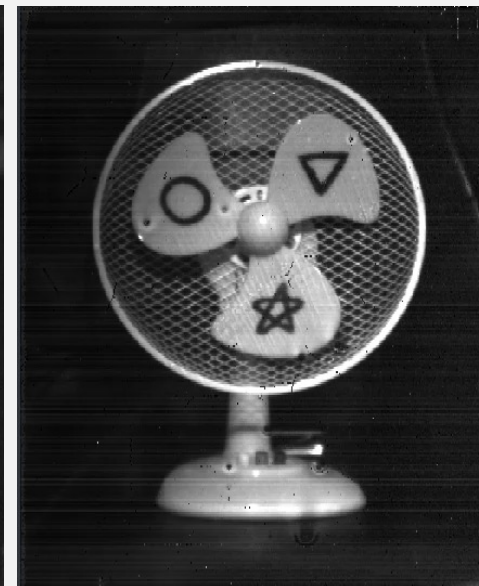


CIS webcam (VIS)

Global shutter operation



Rolling shutter



Global shutter

Food sorting (stones among coffee beans)

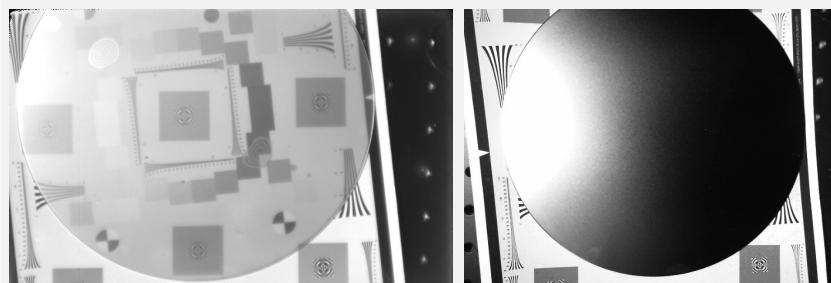


QD imager (SWIR)



CIS webcam (VIS)

Wafer inspection (detection of voids after bonding)



QD imager (SWIR)

CIS webcam (VIS)

Package inspection (see-through)



QD imager (SWIR)



CIS webcam (VIS)

Work in Progress - Improving Image Quality

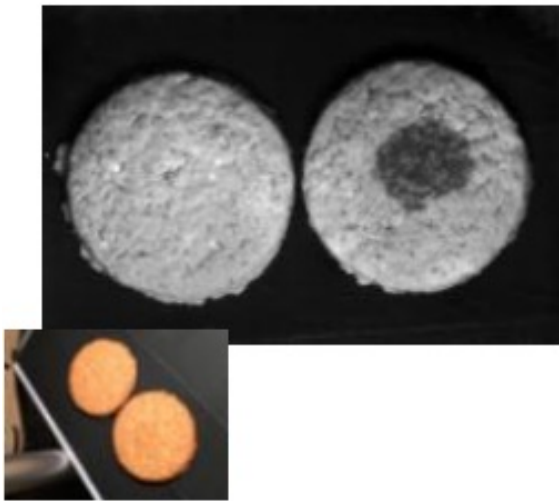
2018

The first QDPD image



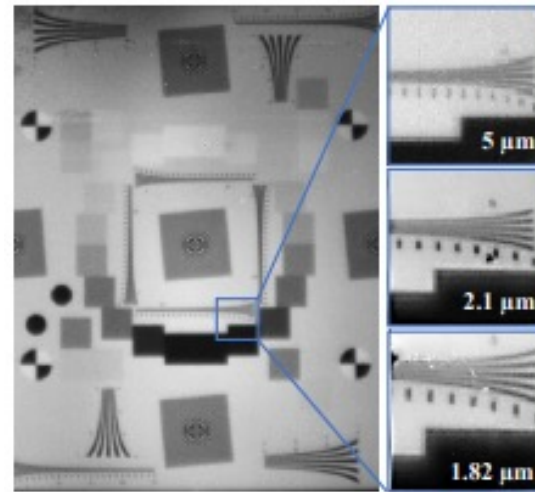
2019

5 μ m SWIR imager (VGA)



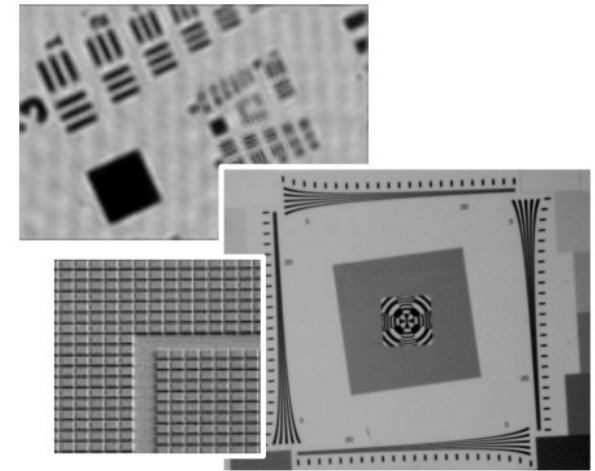
2020

Smallest pitch SWIR (1.82 μ m)



2021

EQE>40%, wafer level pixelation

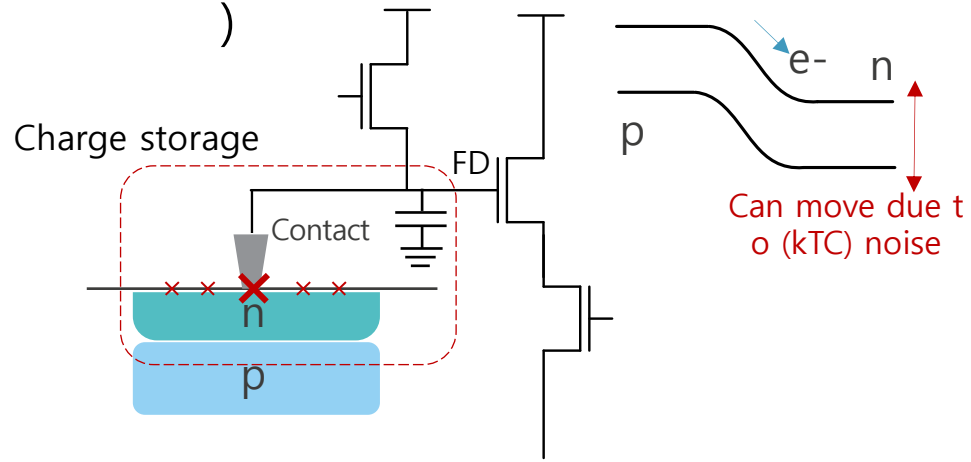


What next?

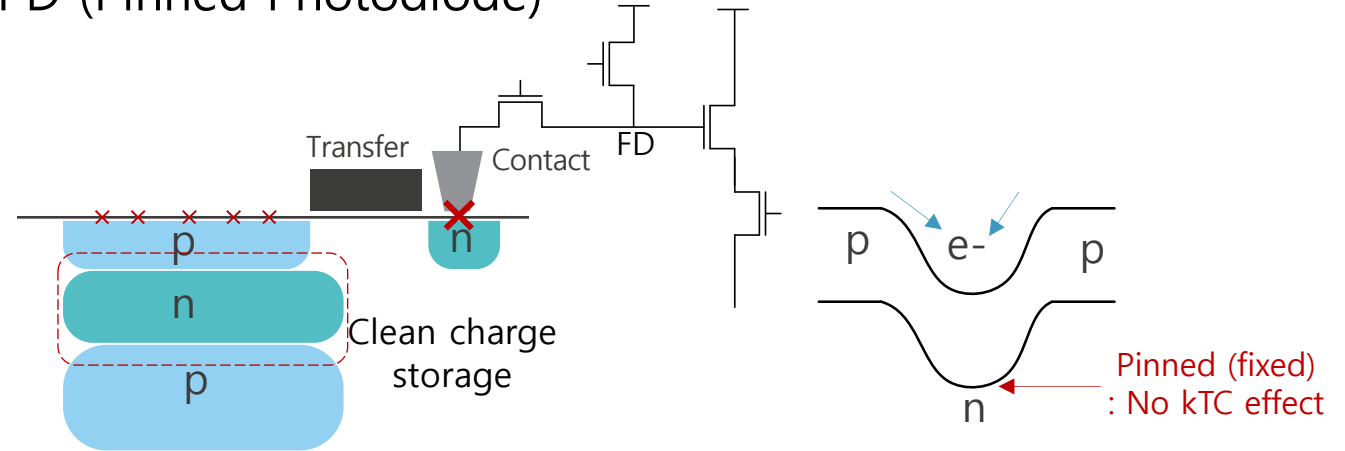
➔ Noise reduction for SNR improvement

Today Main Mainstream Silicon Image Sensor

- PD (Photodiode)



- PPD (Pinned Photodiode)



Requirements: Separation of PD from FD (e-to-V conversion node)

Reset Level Pinning → no-KTC noise

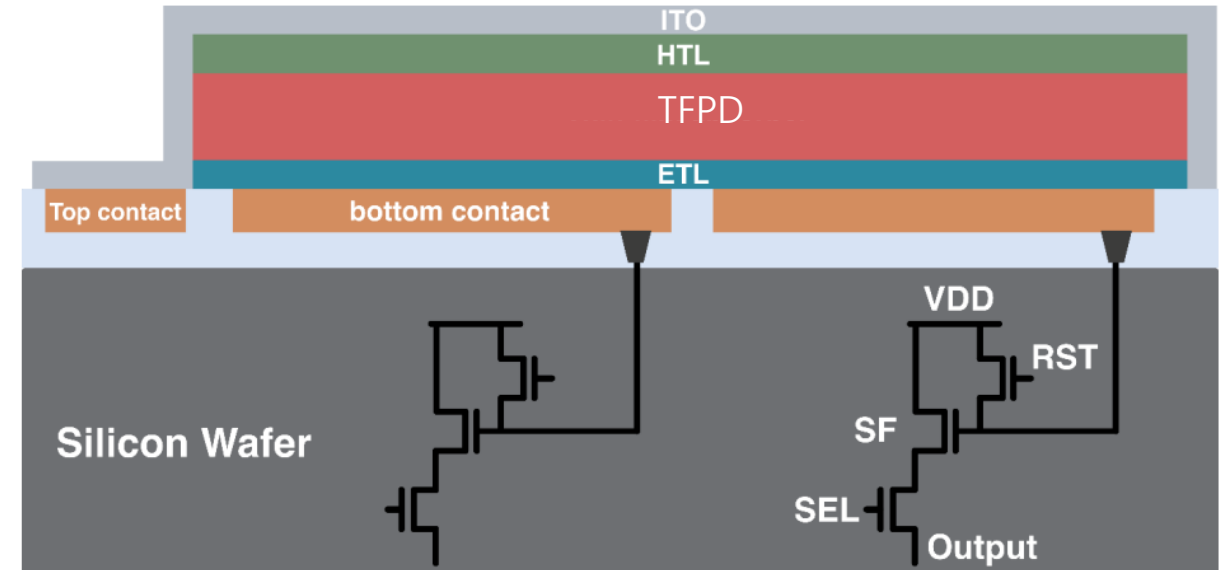
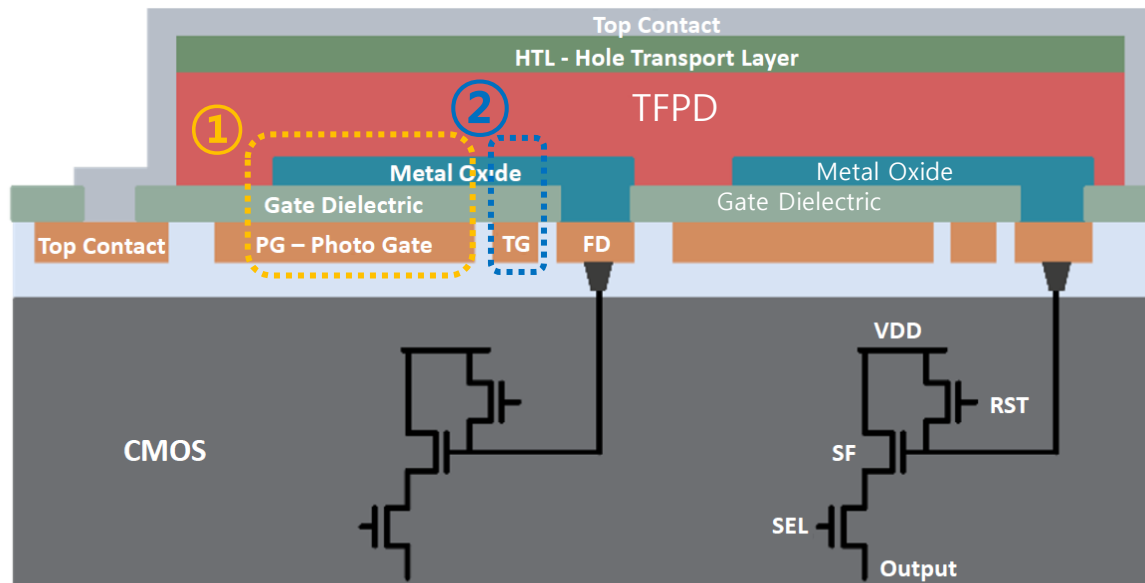
"Further refinement and widespread [adoption of the PPD in CMOS image sensors](#) occurred in the early 2000's and helped CMOS APS achieve imaging performance on par with, or [exceeding, CCDs](#)."

- by Eric R. Fossum from 'A review of the pinned photodiode for CCD and CMOS image sensors' 2014

- **Non-Silicon PPD hasn't been demonstrated yet.**

The First Thin-film PPD (Pinned Photodiode)

- Co-integration of TFT and Thin-film PD on Si-ROIC
 - **Photogage (PG)**: MOS + TFPD → To fix PD reset potential
 - **Transfer Gate (TG)**: To separate PD from e-to-V conversion node (FD)

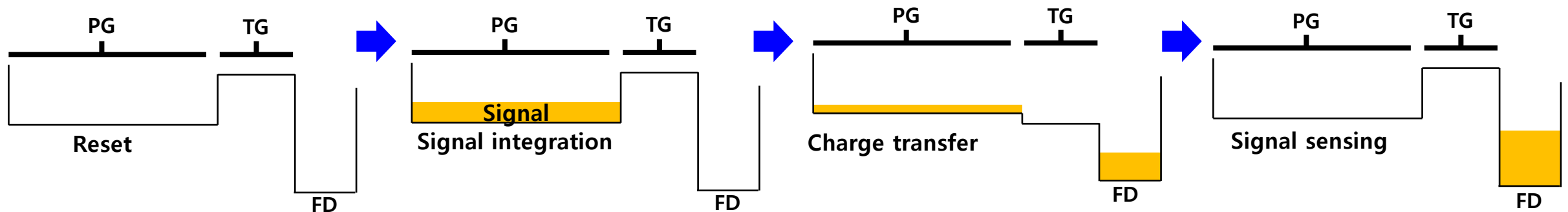
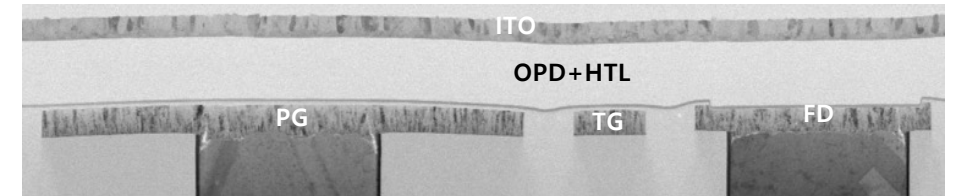
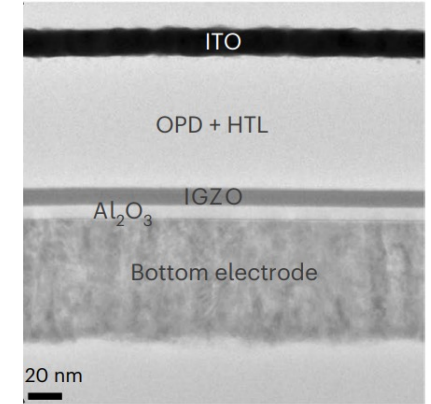
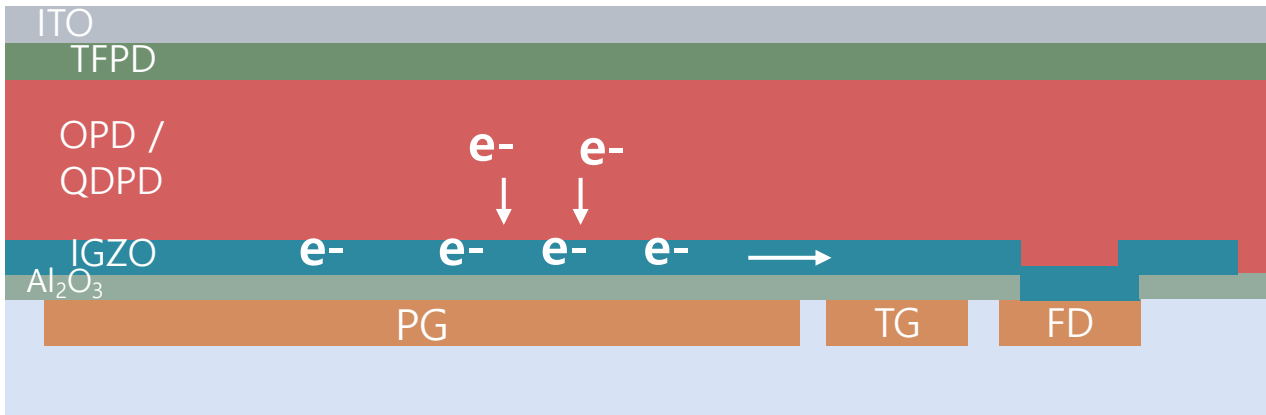


nature electronics

J.Lee et. al., Nature electronics 2023 (<https://doi.org/10.1038/s41928-023-01016-9>)

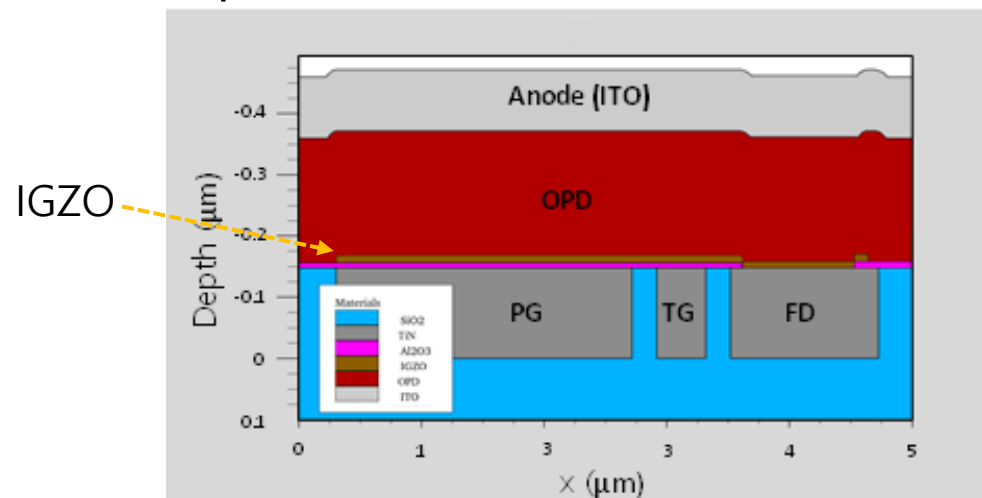
Operation: TF-PPD

- Photo-generated charges move to IGZO and integrated
- Charge transfer when TG open

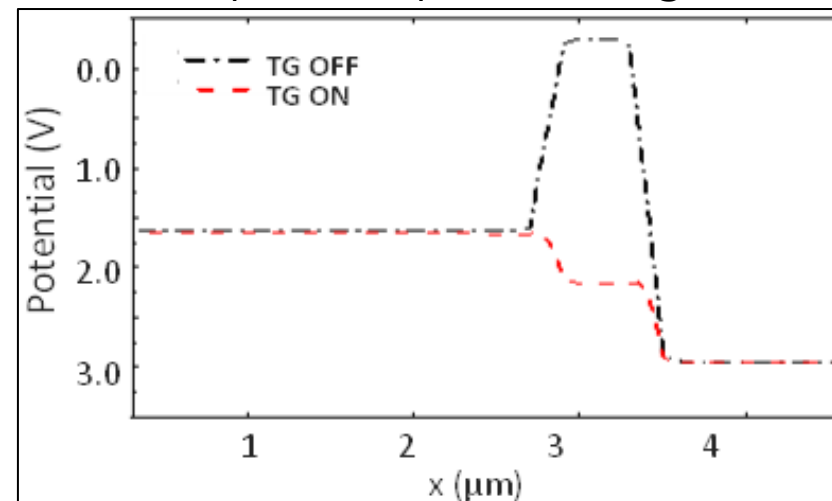


TCAD Simulation

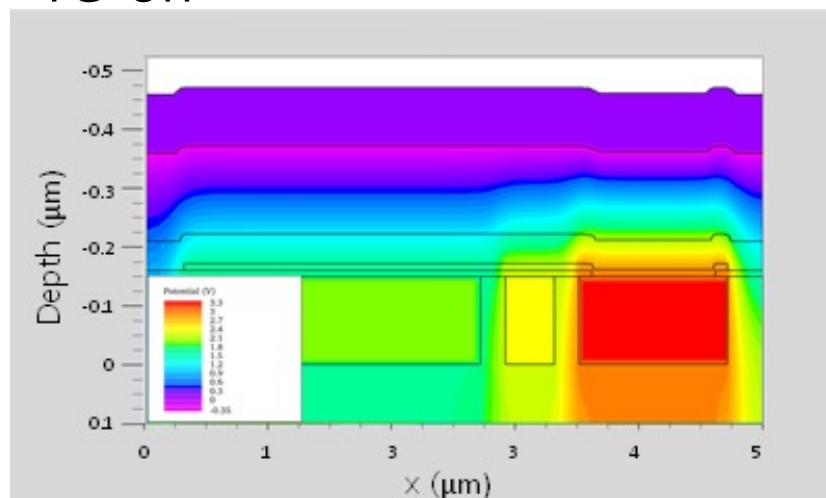
5 μ m Pixel structure (SILVACO)



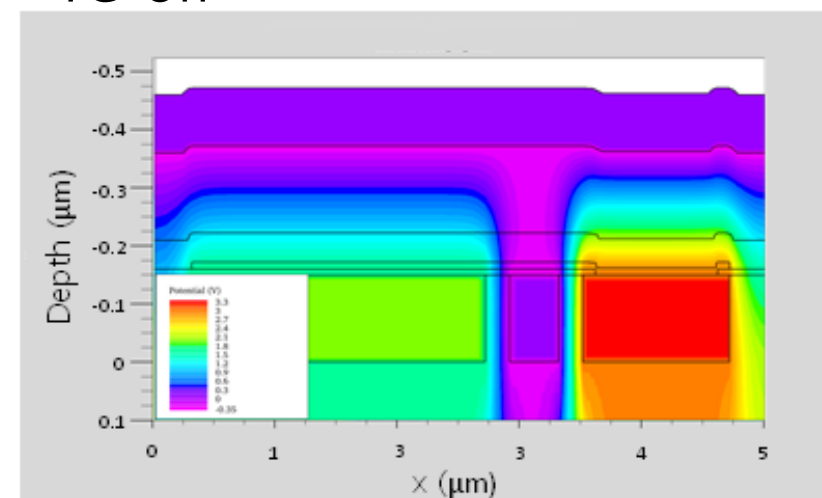
Horizontal potential profile through IGZO



TG on

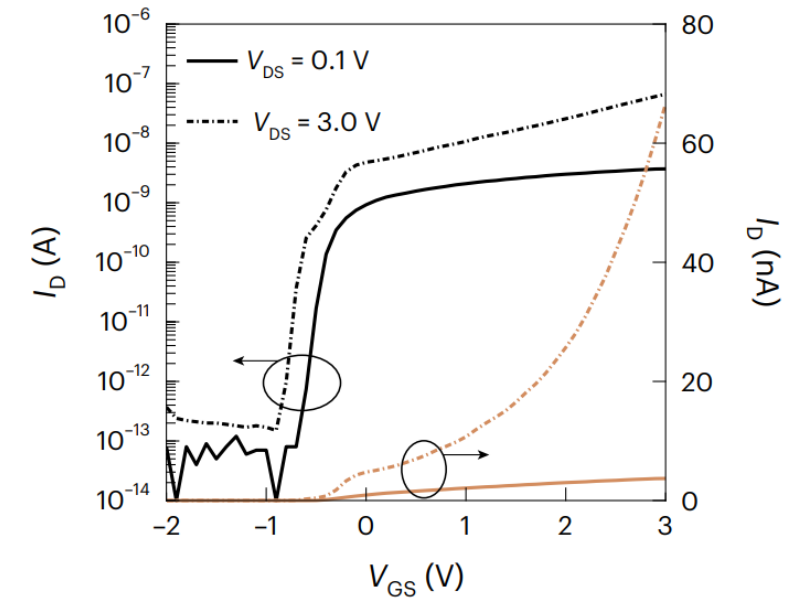
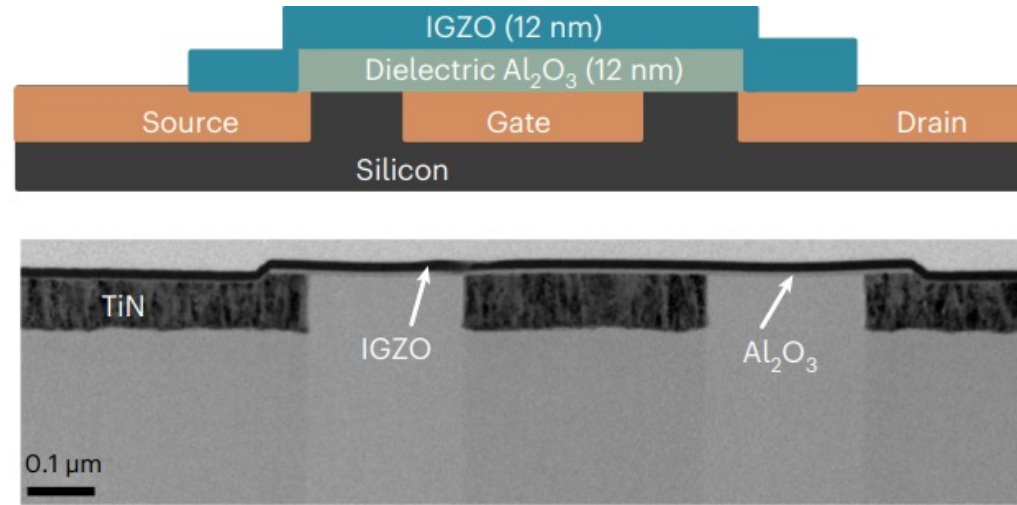
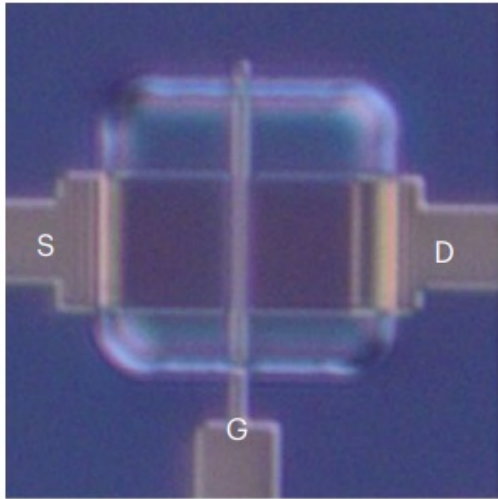


TG off



Back gate, Back SD TFT

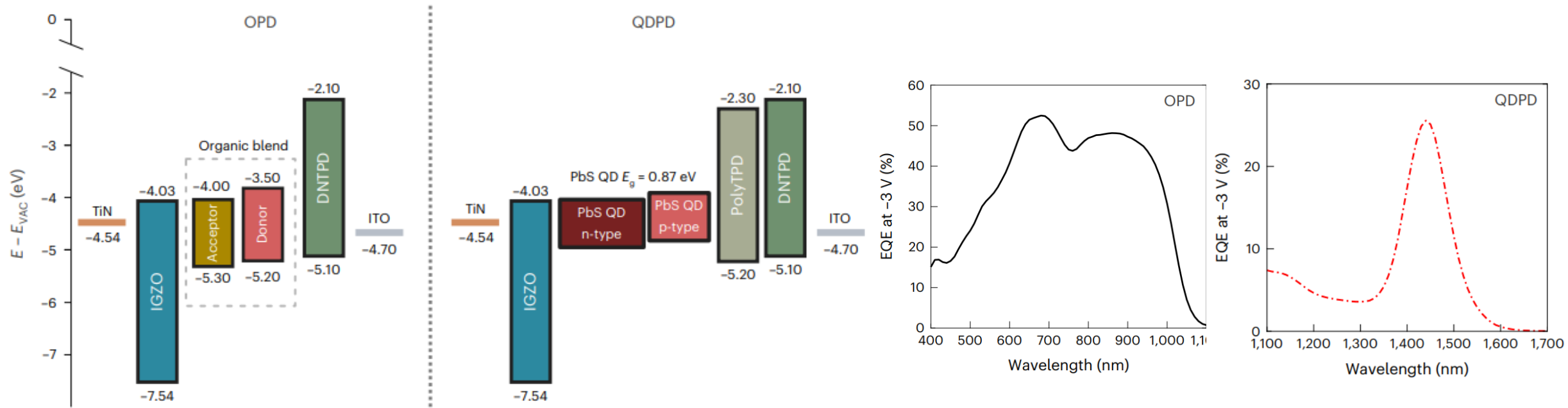
- To directly integrate TFPD on top
 - $V_{th} = -0.5V$, $SS=90mV/dec$



Photodiode Stack

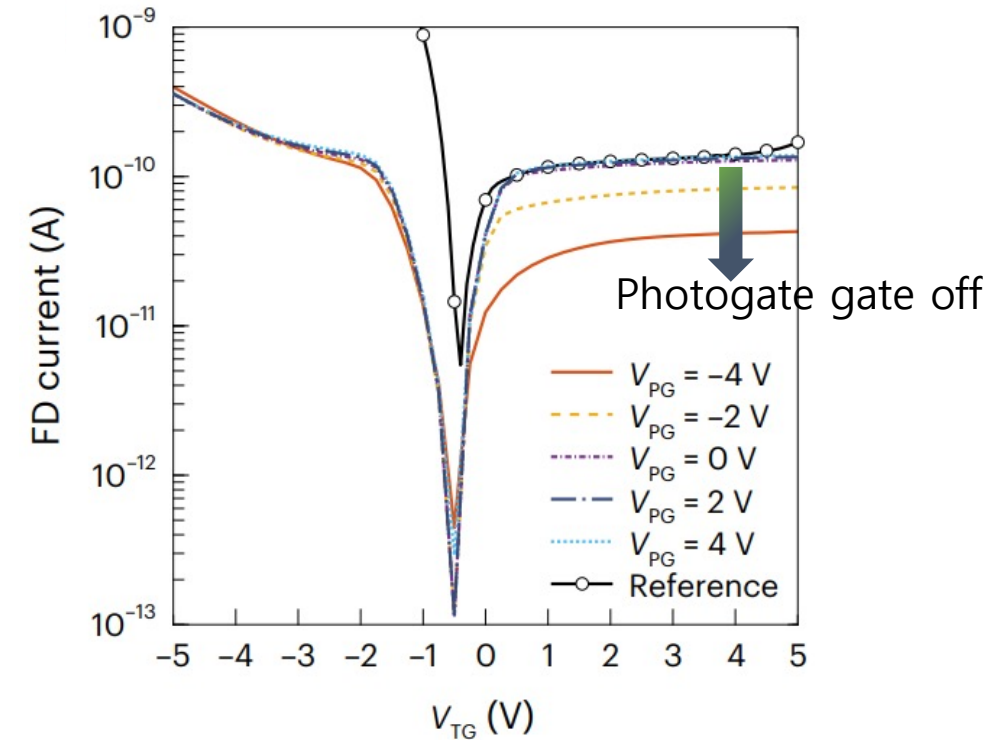
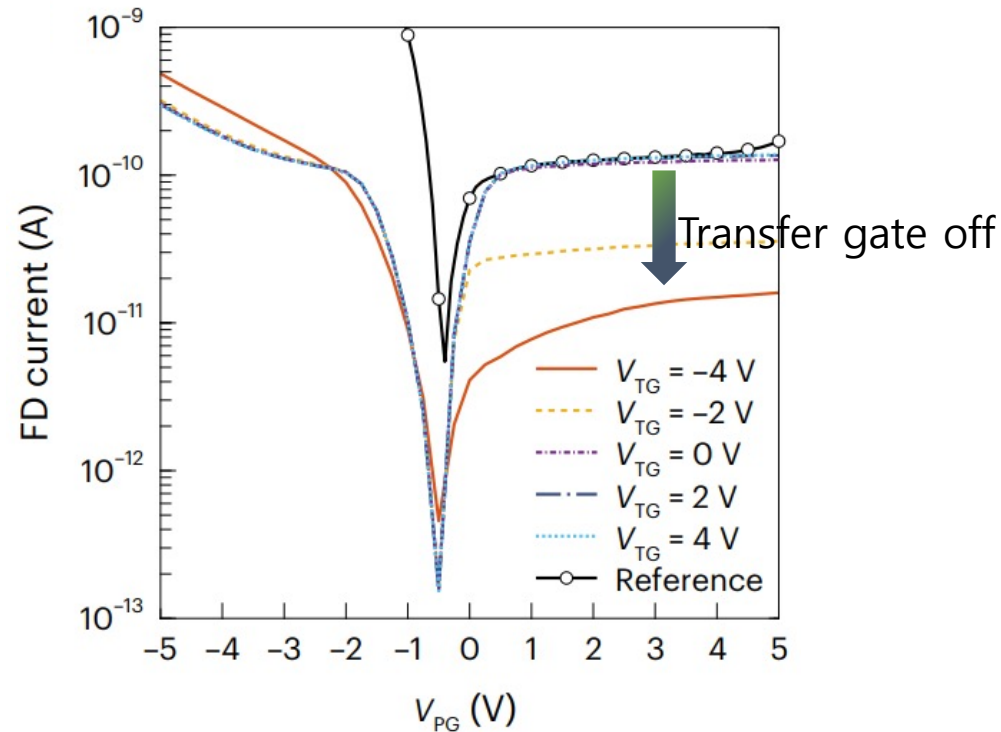
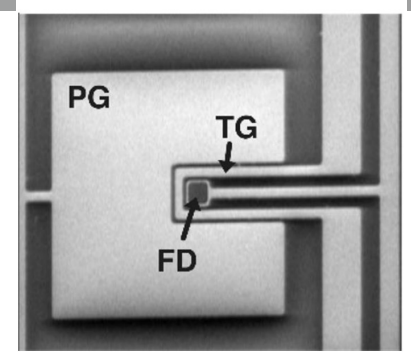
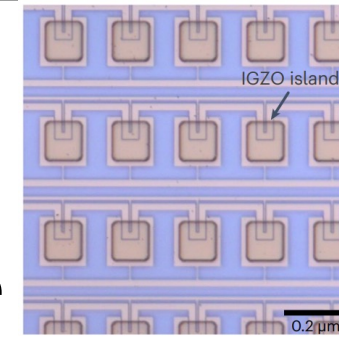
OPD and QDPD example of TF-PPD

- OPD: about 40% EQE at 1,000nm
- QDPD: 26% EQE at 1,450nm



Photogate and Transfer gate operation

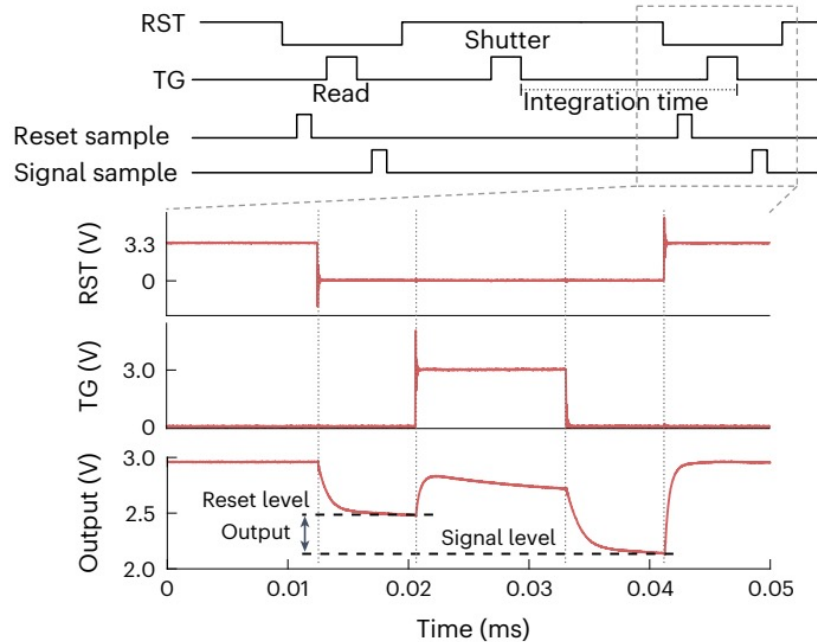
- Operation:
 - PD potential modulation by Photogate
 - Charge accumulation and transfer by Transfer Gate



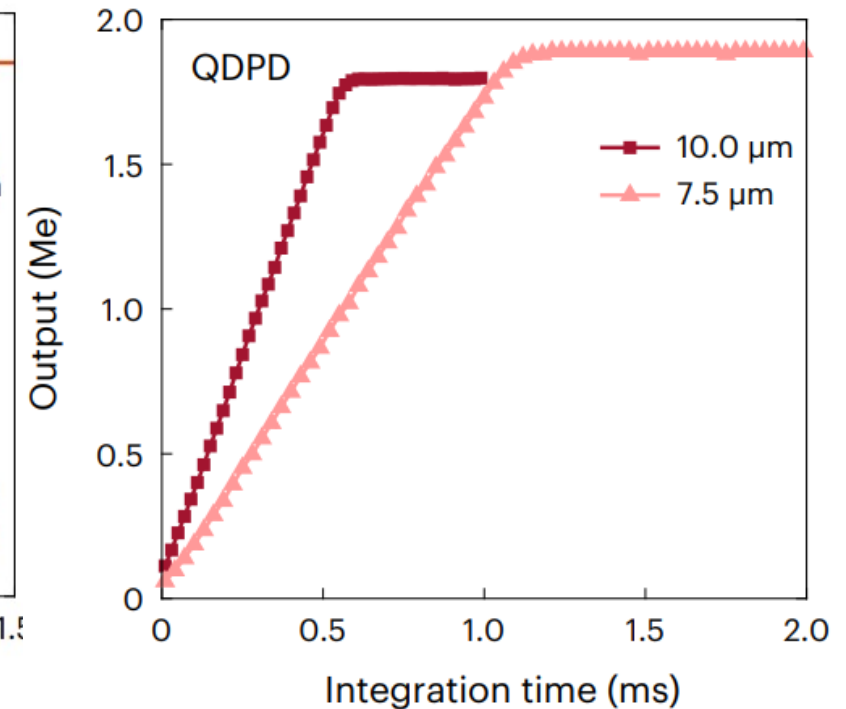
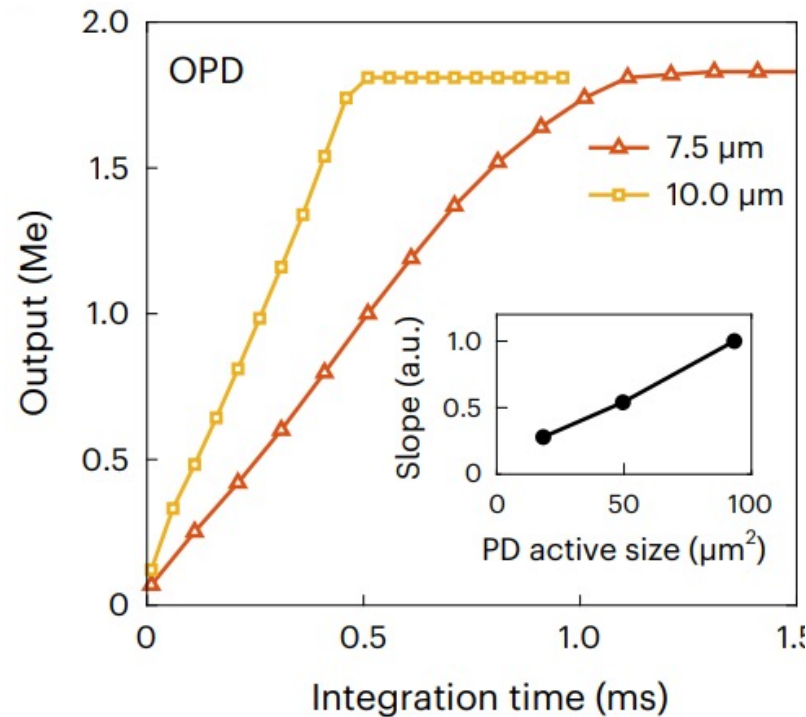
Charge integration and transfer

- Charge transfer operation, linear operation

Operation timing diagram

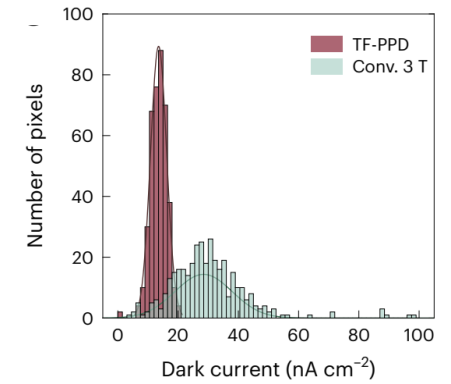
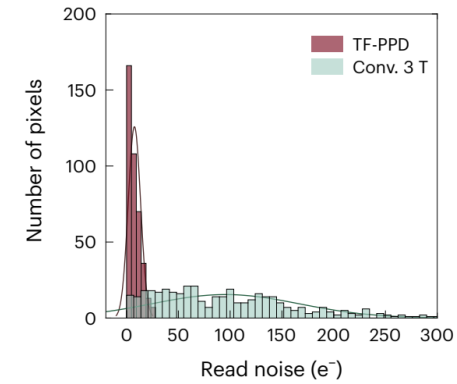


Output vs. integration time



TF-PPD Demonstration (W/ OPD)

- Better image quality with reduced noise



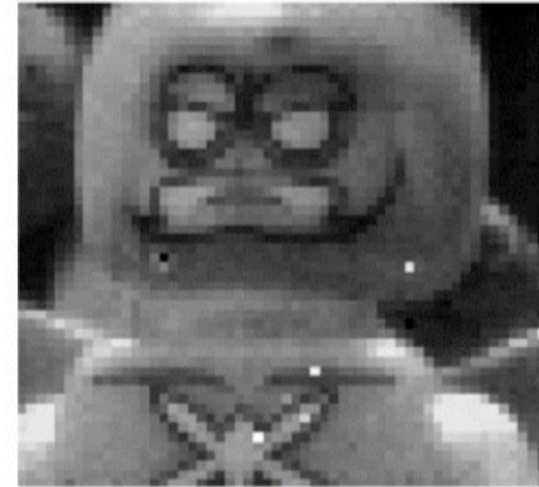
Reference



Conv. 3T



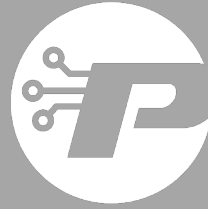
TF-PPD



acquired under the same conditions

Summary

- State-of-the-art Silicon Image Sensors to approach the theoretical limits of classical photography
- Shortwave infrared (SWIR) is becoming important for efficient information sensing.
- Quantum dot photodiode offer a cost-effective solution for high-resolution SWIR image sensors.
- The first TF-PPD has been demonstrated:
 - Low noise, low dark current, high conversion gain



반도체공학과

POSTECH
